



SEE induced by heavy ions and laser pulses in Si Schottky diodes

RADLAS 2017

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(1) TRAD – (2) INSA/LPCNO – (3) CNES – (4) Thales Alenia Space

▪ Context of the study

- ▶ First destructive events in Schottky diodes : 2011 [Casey,2014]
- ▶ Laser tests for SEE sensitivity prediction or initial sorting
- ▶ Derating rules

▪ Funding

- ▶ Framework : CNES (R&T)
- ▶ Tests & analysis : TRAD / INSA LPCNO / THALES Alenia Space
- ▶ Heavy ion beam-time : CNES / ESA

▪ Objectives

- ▶ Laser / heavy ions comparison in simple structures
- ▶ Impact of optical parameters

▪ Outline

1. Test methods
2. SEB in Schottky diodes
3. Heavy ion tests
4. Laser tests

Conclusion

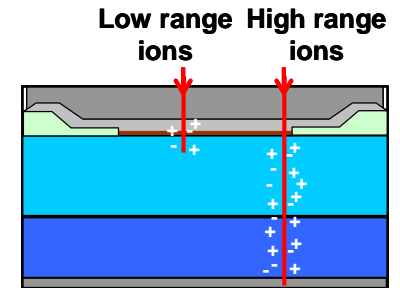
- **Heavy ion tests performed at UCL and GANIL**

- ▶ **Low range tests: UCL**

(Université Catholique de Louvain, Belgium)

- ▶ **High range tests: GANIL**

(Grand Accélérateur Nat. d'Ions Lourds, France)



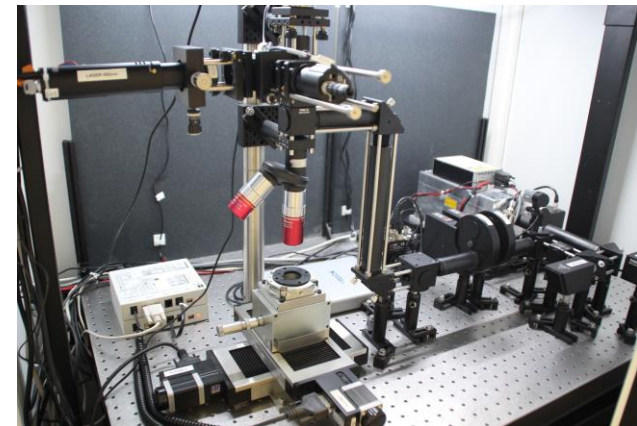
- **Laser tests performed at TRAD laser facility**

- ▶ **Laser**

- Active Q-switched
 - Wavelength 1.064 μ m
 - Pulse duration 400ps
 - Single shot to 50kHz
 - Beam waist 0.9 μ m, 1.3 μ m, 4 μ m

- ▶ **3-axis motorized linear stages**

- ▶ **Visible camera + 850nm positioning laser**

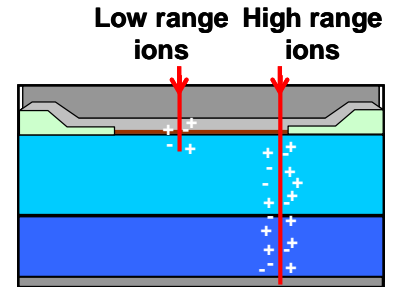


TRAD Laser facility

LISA (Laser Irradiation tool for SEE Analysis)

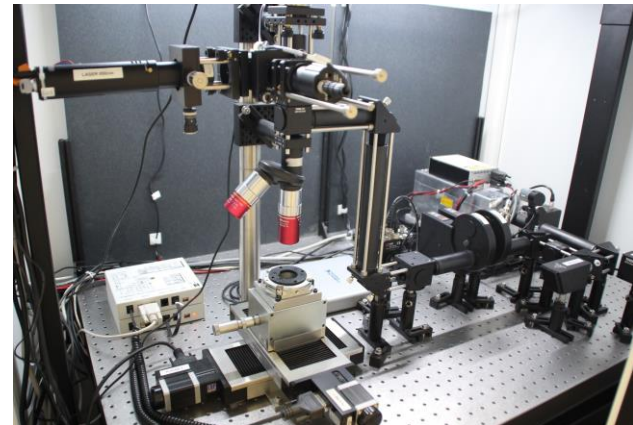
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TRAD Laser facility

LISA (Laser Irradiation tool for SEE Analysis)

■ Test set-up

- ▶ **Single Measure Unit**
 - Polarization and leakage current measurements
 - Resolution : < 250ms
- ▶ **No additional capacitor or resistance**
- ▶ **Identical for both heavy ion and laser tests**

- Devices tested : planar and trench Si Schottky diodes from *OnSemiconductor*

MBRF10L60CTG

$V_{RRM}=60\text{ V}$ (max reverse voltage)

Planar structure

« Classical » diode structure

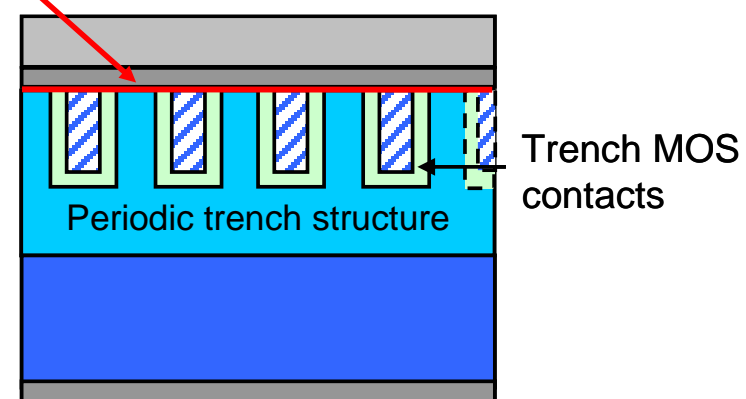
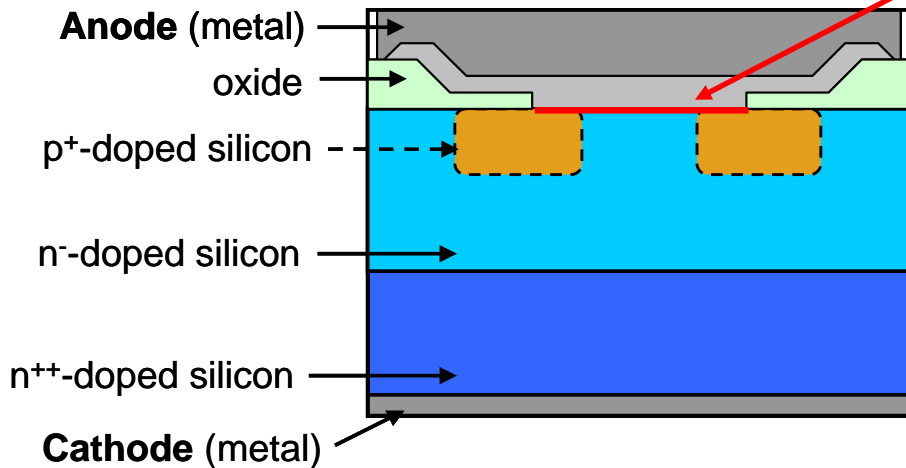
NTST20120CTG

$V_{RRM}=120\text{ V}$ (max reverse voltage)

Trench structure

A new electric field distribution to improve electrical performances

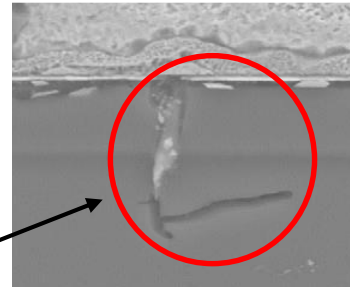
Schottky contact



▪ **SEB in reverse polarized planar Schottky diodes (heavy ion tests)**

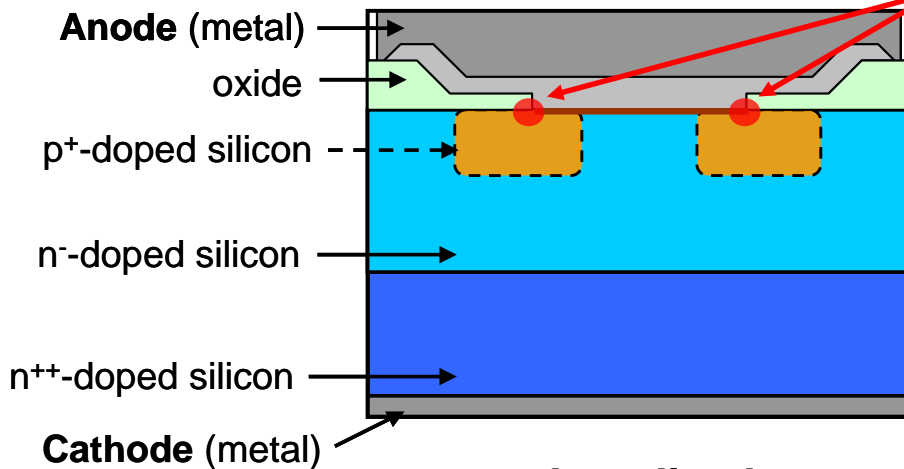
[George,2013] [Theiss,2015] [Casey,2017]

- Charge injection
- Impact ionization
- Local temperature increase
- Thermal runaway → **local fusion**

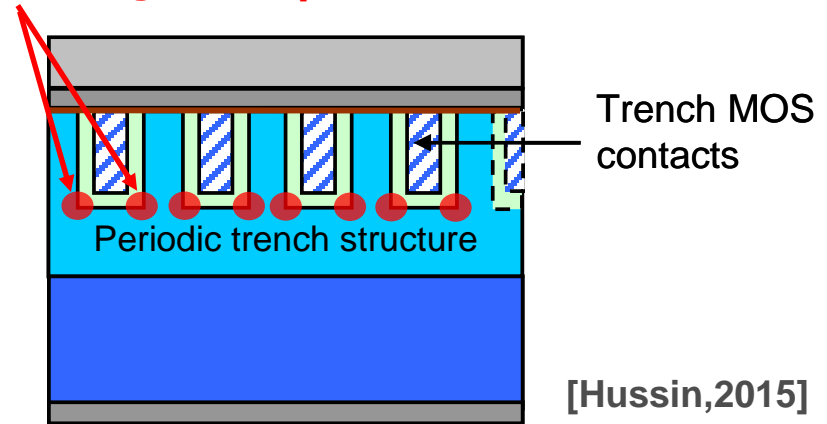


[Casey,2017]

Highest electric field regions → probable sensitive areas



Localized spatial sensitivity



[Hussin,2015]

Periodic spatial sensitivity

Heavy ion testing

➤ Destructive events at low range (< 300µm)

▫ Planar diode

from LET = 45MeV.cm².mg⁻¹ @ V_R = 100% V_{RRM}

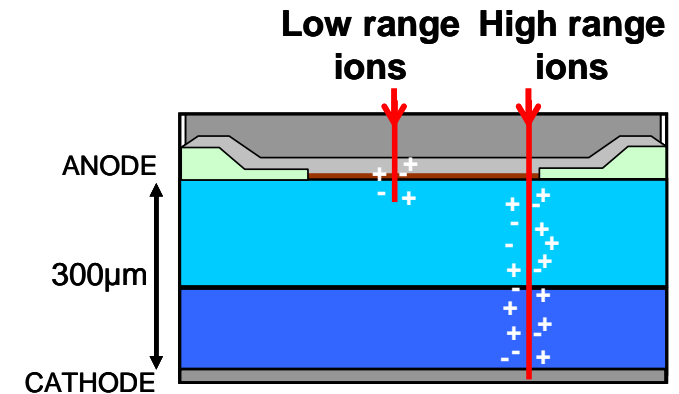
▫ Trench diode

from LET = 20MeV.cm².mg⁻¹ @ V_R = 90% V_{RRM}

→ Trench = more sensitive

➤ Destructive events at high range (> 300µm)

▫ Increase of the sensitivity → anode/cathode electrical short circuit ?



Xe : LET = 32.4MeV.cm².mg⁻¹

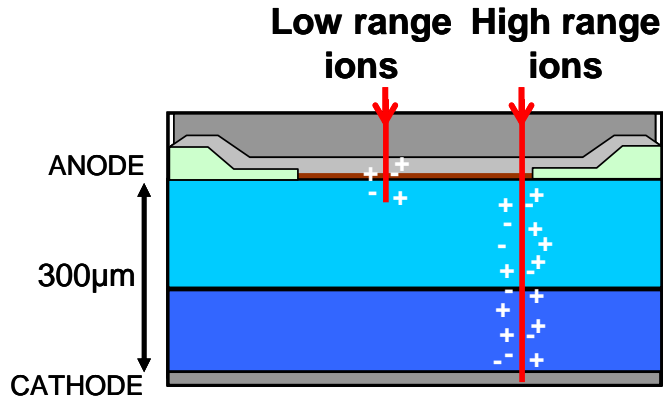
Ref.	LOW RANGE	HIGH RANGE
Planar MBRF10L60CTG	PASS @ 100%V _{RRM}	FAIL @ 100%V _{RRM}
Trench NTST20120CTG	PASS @ 75%V _{RRM}	FAIL @ 75%V _{RRM}

V_{RRM} : max. reverse voltage

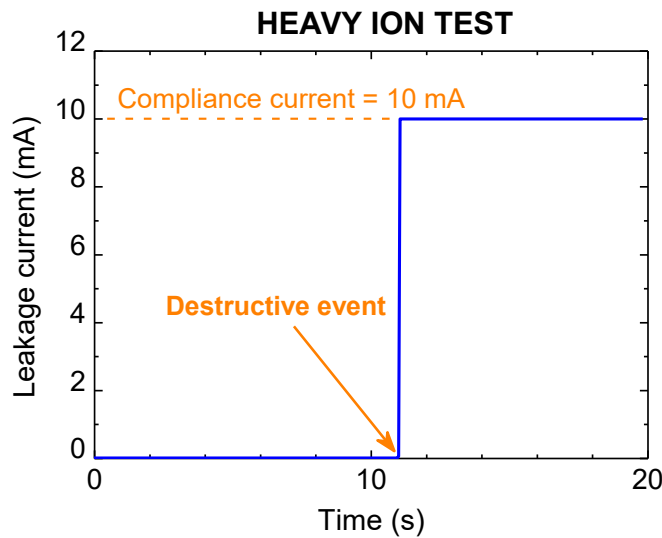
➔ Interest of laser tests (high range)

Test conditions

$$V_R = 100\%V_{RRM}$$

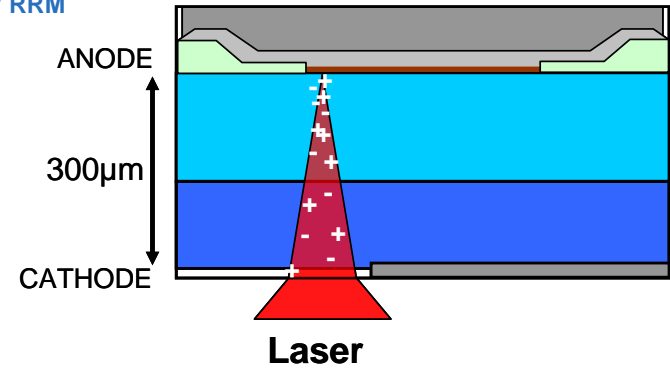
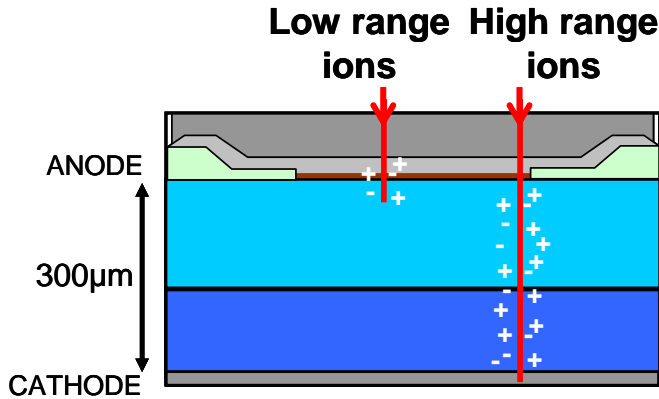


Leakage current behaviour

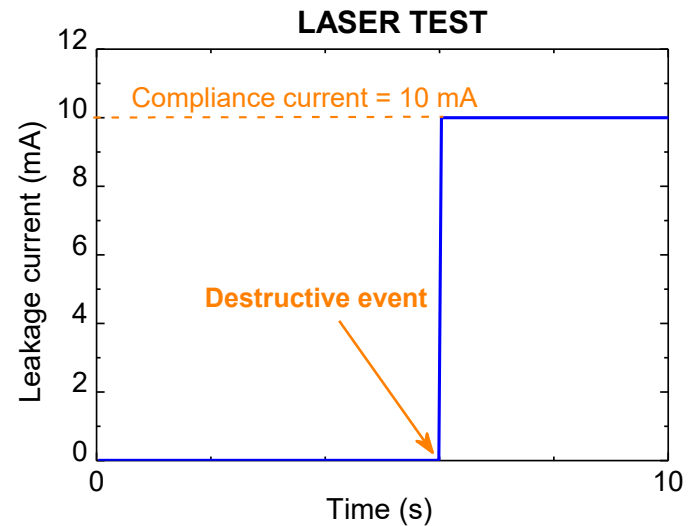
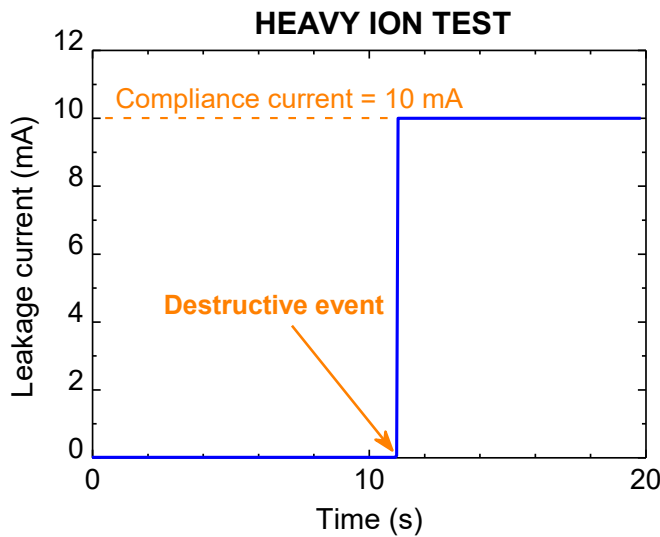


Test conditions

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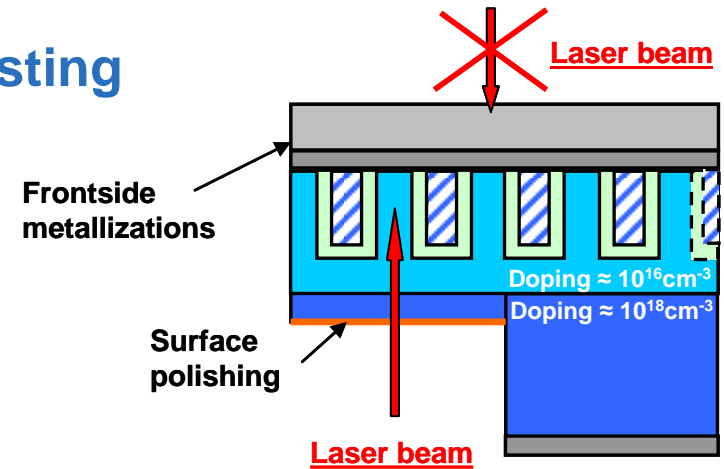
Leakage current behaviour



Destructive event triggered by laser pulse

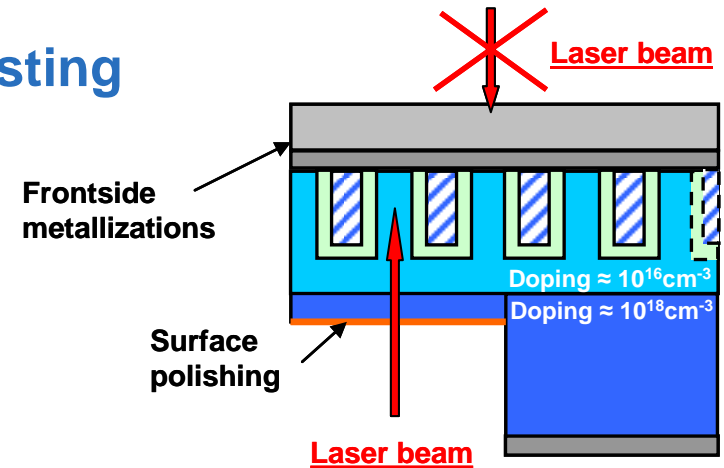
■ Backside device preparation for laser testing

- ▶ **Delidding**
- ▶ **Thinning : $\sim 130\mu\text{m}$**
 - Maximization of the sensitive area accessibility
 - Preservation of the electrical performances
- ▶ **Polishing**



Backside device preparation for laser testing

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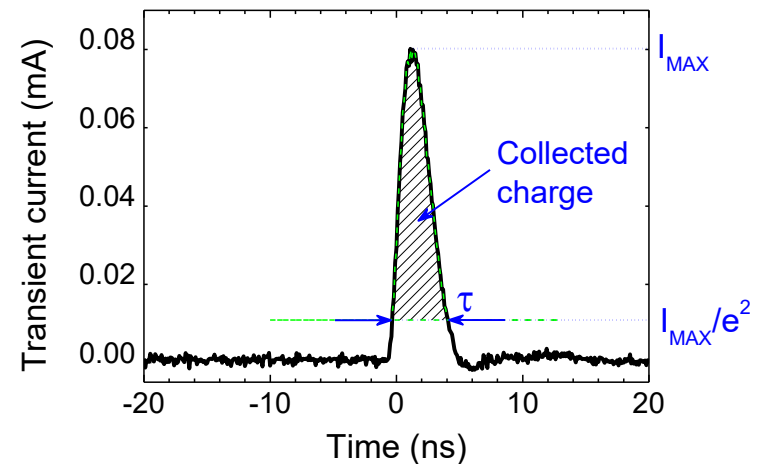


Transient photocurrent measurements below SEB threshold

Decoupled power supply, 4GHz oscilloscope connected with SMA cable

- ▶ Average transient duration @ $1/e^2$
- ▶ Average collected charge @ $1/e^2$
 - Mainly from drift currents
 - linked with destructive events

Dependence on energy, focusing depth, reverse voltage



■ Collected charge : laser energy dependence

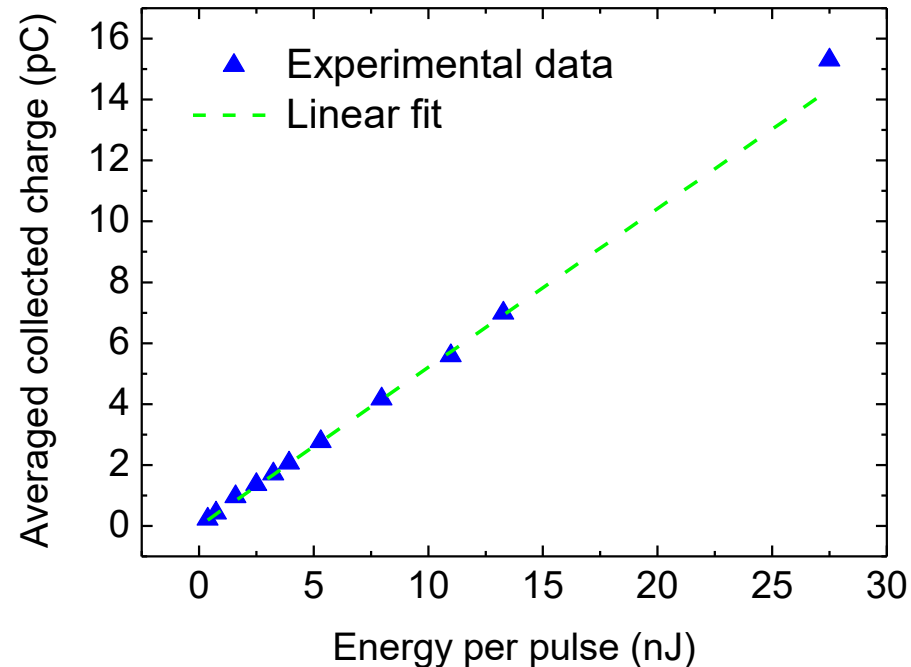
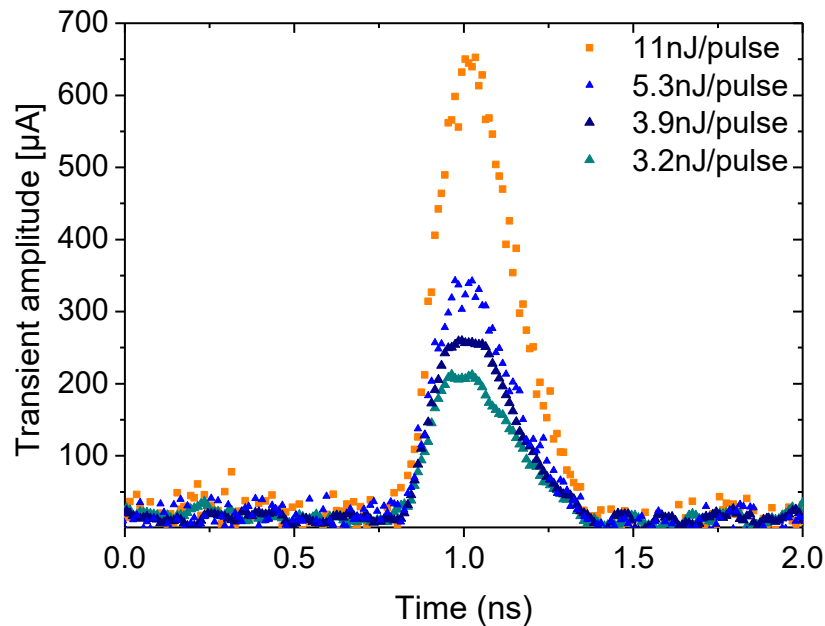
$$\lambda = 1.064\mu\text{m}$$

$$N_D < 10^{17} \text{ cm}^{-3}$$

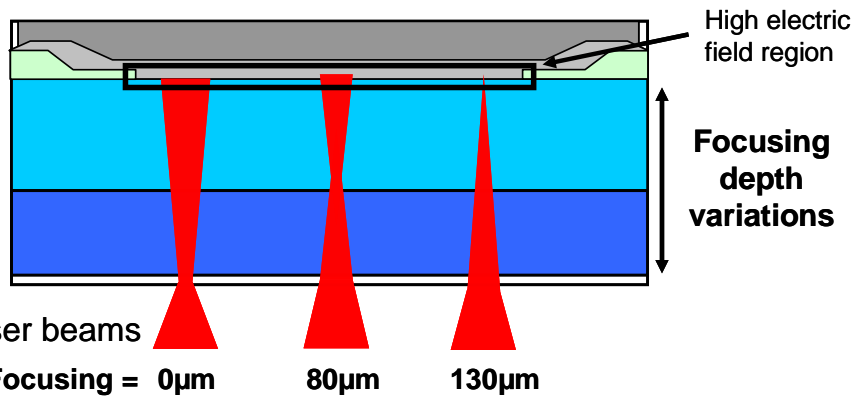
→ two photon absorption **negligible**
(10^{10} times less than single photon abs.)

→ intraband absorption **negligible**

→ main absorption process = **single photon absorption**
linear dependence with energy



■ Laser focusing depth dependence



- ▶ Collected charge mainly due to drift currents (in the depletion region)

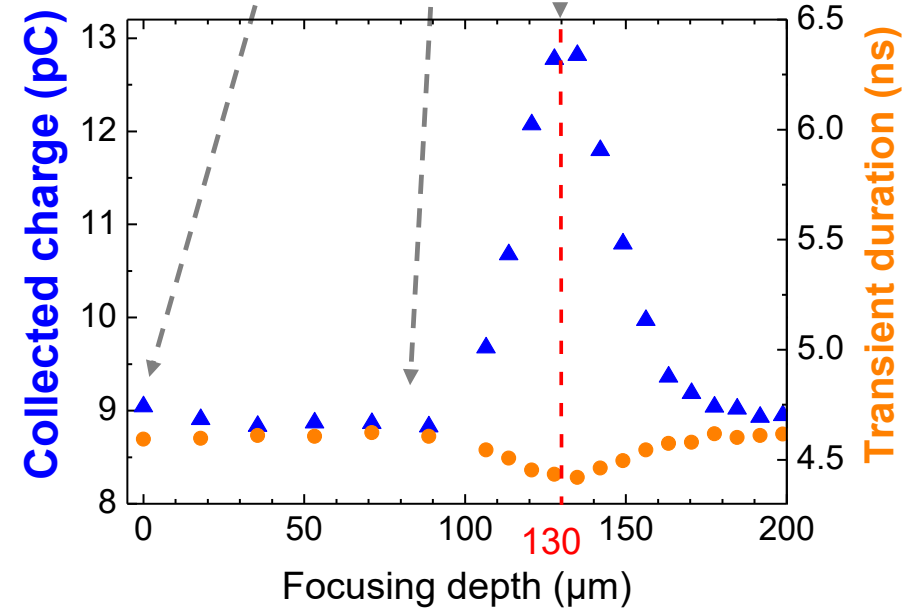
▶ Analysis

Focusing depth close to the depletion region

Maximization of drift currents

- transport efficiency increase
- charge velocity increase (electric field)
- potential impact ionization

➔ **Increase of collected charge (+50%)**
Decrease of transient duration (-5%)



■ Laser test : reverse voltage dependence (focusing depth = depletion region)

► Collected charge mainly due to drift currents (in the depletion region)

► Analysis

Increase of reverse voltage (V_R)

$$\propto V^{1/2}$$

$$\propto V^{1/2}$$

Increase of depleted region thickness (W)

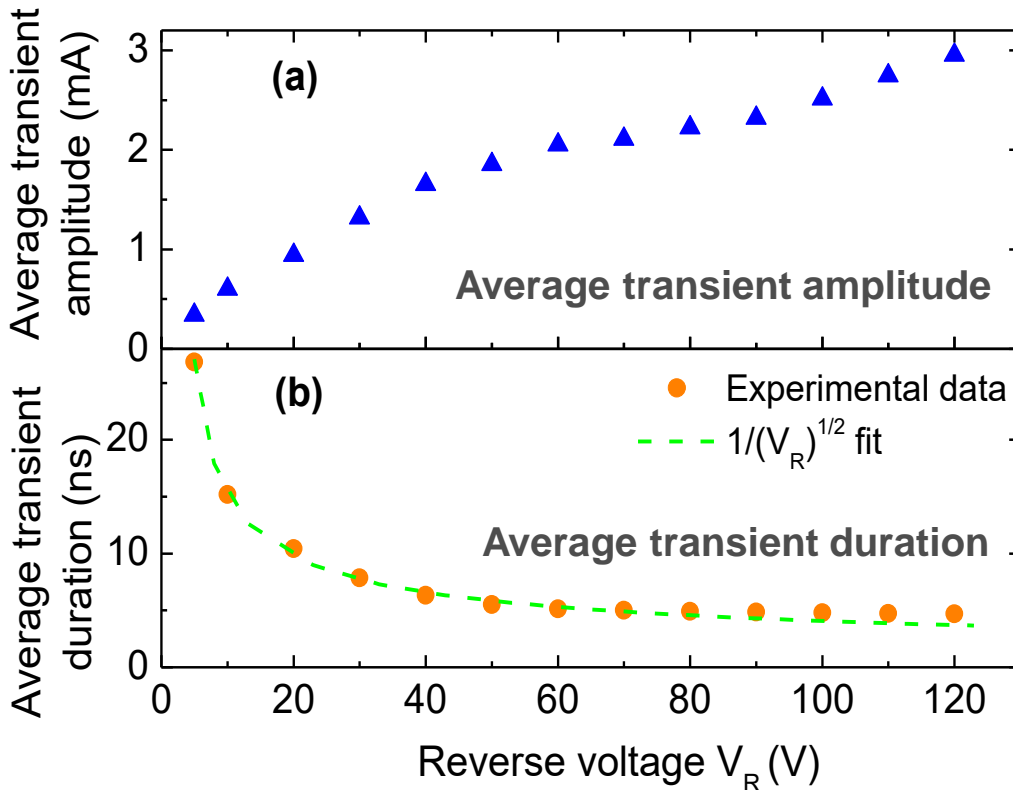
Increase of electric field
(impact ionization)

$$\propto V^{1/2}$$

Increase of the collection volume
(collected charge)

Increase of the charge velocity
(transient duration)

Increase of the sensitivity



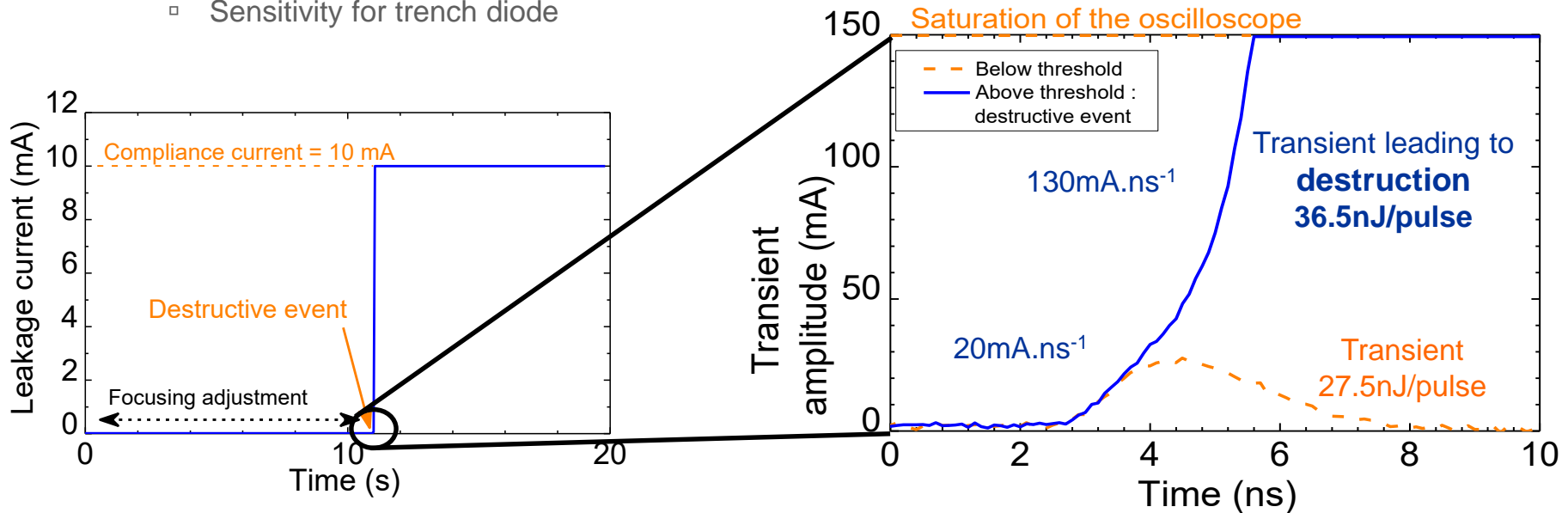
■ Laser testing in PLANAR diode

- ▶ Collected charge < 25 times less than expected (< 0.1pC)
→ No destructive event

Laser energy above SEB threshold

■ Laser testing in TRENCH diode

- ▶ Critical parameters to trigger events :
 - Energy, reverse voltage, ⚠ focusing depth
- ▶ Reproducible destructive events at 36.5nJ/pulse @100% V_{RRM}
- ▶ Comparison with heavy ion tests :
 - Destructive signature comparable to heavy ions
 - Sensitivity for trench diode

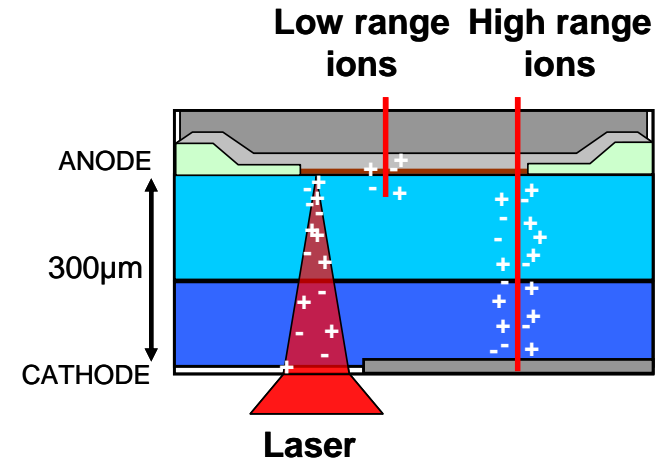


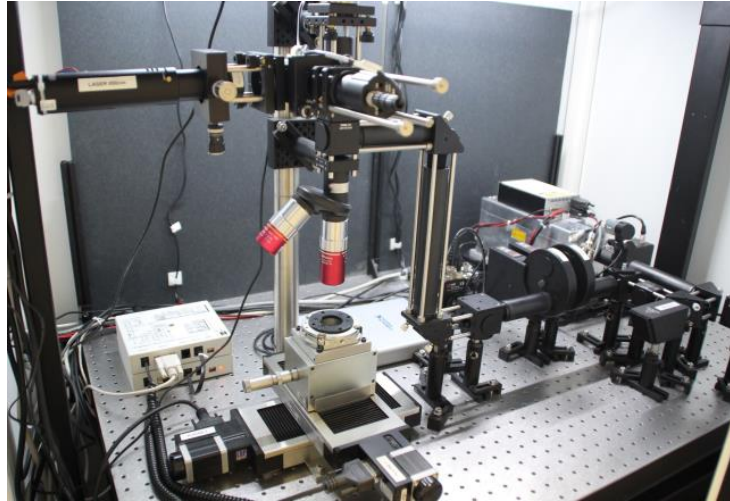
■ One-photon laser testing for Si Schottky diodes

- Reproducible destructive events
- Comparison with heavy ion test results
 - Destructive signature
 - Electrical parameters
- Important impact of doping levels and structures

■ Further studies for heavy ions / laser correlation

- Transient measurements during heavy ion tests
 - LET / laser energy SEB threshold
- TCAD with photogeneration and transport model
 - To further understand laser test results
- Laser tests
 - Spatial sensitivity study
 - Other planar and trench references





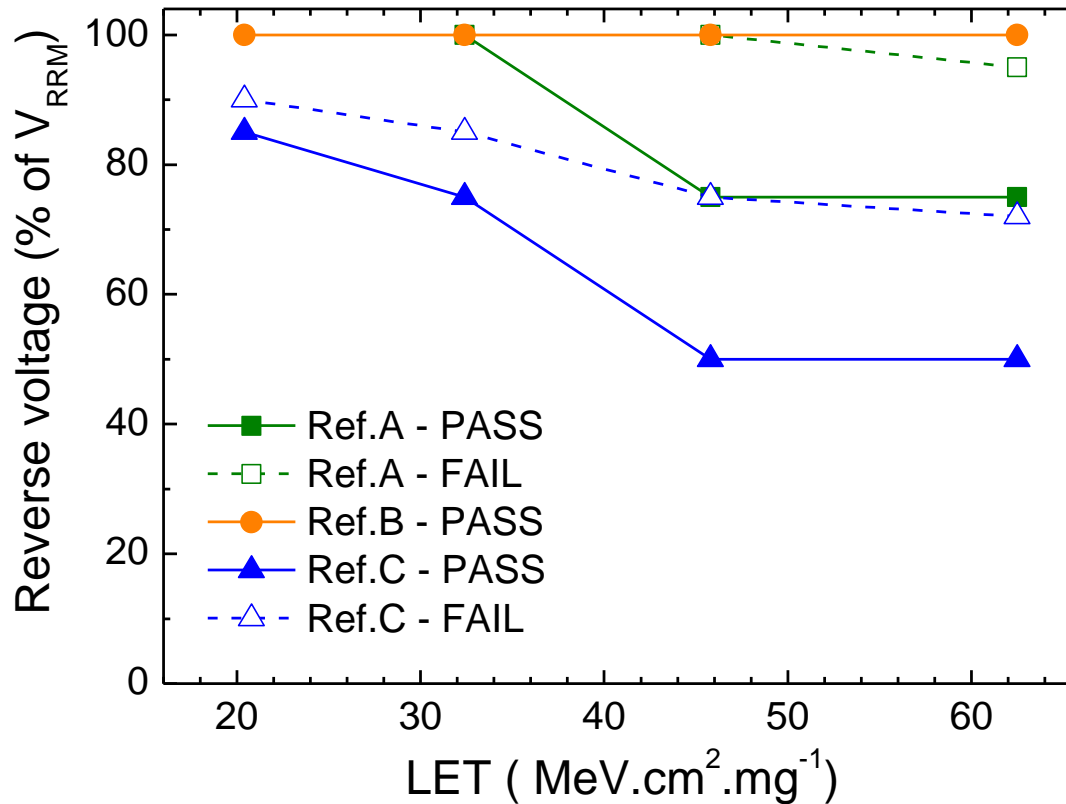
Thank you

Questions ?

Additional material

Heavy ion test results

- Performed at UCL (Université Catholique de Louvain, Belgium)



Photogenerated collected charge

- ▶ Based on an SPA analytical model from [Buchner,2013]
- ▶ Funneling extension and collection efficiency neglected
- ▶ Collected charge : a few pC

